

WHAT IS CLAIMED IS :

1. A perfluoropolyether comprising perfluoroalkyl radical end groups having at least 3 carbon atoms per radical and is substantially free of perfluoromethyl and perfluoroethyl end groups, and 1,2-bis(perfluoromethyl)ethylene diradical [-CF(CF₃)CF(CF₃)-] is absent in the molecule.
- 5 2. A perfluoropolyether according to claim 1 wherein said perfluoroalkyl radical has 3 to 6 carbon atoms per radical.
- 10 3. A perfluoropolyether according to claim 1 wherein said perfluoropolyether has the formula of C_rF_(2r+1)-A-C_rF_(2r+1); each r is independently 3 to 6; if r = 3, both end groups C_rF_(2r+1) much be n-propyl radical; A is selected from the group consisting of O-(CF(CF₃)CF₂-O)_w, O-(C₂F₄-O)_w, O-(C₂F₄-O)_x(C₃F₆-O)_y, O-(CF₂CF₂CF₂-O)_w, and combinations of two or more thereof; w is 4 to 100; x, y, and z are each independently 1 to 100.
- 15 4. A composition comprising a perfluoropolyether, which comprises perfluoroalkyl radical end groups having at least 3 carbon atoms per radical and is substantially free of perfluoromethyl and perfluoroethyl end groups, and 1,2-bis(perfluoromethyl)ethylene diradical [-CF(CF₃)CF(CF₃)-] is absent in the molecule.
- 20 5. A composition according to claim 4 wherein said perfluoroalkyl radical has 3 to 6 carbon atoms per radical.
6. A composition according to claim 4 wherein said perfluoropolyether has the formula of C_rF_(2r+1)-A-C_rF_(2r+1); each r is independently 3 to 6; if r = 3, both end groups C_rF_(2r+1) much be n-propyl radical; A is selected from the group consisting of 25 O-(CF(CF₃)CF₂-O)_w, O-(C₂F₄-O)_w, O-(C₂F₄-O)_x(C₃F₆-O)_y, O-(CF₂CF₂CF₂-O)_w, and combinations of two or more thereof; w is 4 to 100; x, y, and z are each independently 1 to 100.

7. A composition according to claim 4, 5, or 6 wherein said composition further comprises a thickener and said perfluoropolyether is present in said composition in the range of from about 0.1 to about 50 weight % based on said composition.
8. A composition according to claim 7 wherein said thickener is selected from 5 the group consisting of poly(tetrafluoroethylene), fumed silica, and boron nitride, and combinations of two or more thereof.
9. A process comprising (1) contacting a perfluoro acid halide, a C₂ to C₄-substituted ethyl epoxide, a C₃⁺ fluoroketone, or combinations or two or more thereof with a metal halide to produce an alkoxide; (2) contacting said alkoxide with 10 hexafluoropropylene or tetrafluorooxentane to produce a second acid halide; (3) esterifying said second acid halide to an ester; (4) reducing said ester to its corresponding alcohol; (5) converting said corresponding alcohol with a base to a salt; (6) contacting said salt with a C₃⁺ olefin to produce a prepolyether; and (7) fluorinating said prepolyether.
- 15 10. A process according to claim 9 wherein said C₃⁺ olefin is a C₃-C₆ straight chain olefin, C₃-C₆ branched chain olefin, C₃-C₆ allyl halide, or combinations of two or more thereof.
11. A process according to claim 9 wherein said process comprises (1) 20 contacting a perfluoro acid halide or a C₂ to C₄-substituted ethyl epoxide with a metal halide to produce an alkoxide; (2) contacting said alkoxide with hexafluoropropylene or tetrafluorooxentane to produce a second acid halide; (3) esterifying said second acid halide to an ester; (4) contacting said ester with a Grignard reagent to produce a carbinol; and (7) dehydrating or fluorinating said carbinol.
- 25 12. A process according to claim 9 wherein said process comprises (1) contacting a perfluoro acid halide, a C₂ to C₄-substituted ethyl epoxide, a C₃⁺ fluoroketone, or combinations or two or more thereof with a metal fluoride to produce an alkoxide; (2) contacting said alkoxide with hexafluoropropylene or tetrafluorooxentane to produce a second acid fluoride; (3) contacting said second

acid fluoride with lithium iodide to produce an acid iodide; and (4) fluorinating said prepolyether.

13. A process according to claim 12 wherein said process further comprises step (3a) reducing the iodide radical of said acid iodide to corresponding hydrogen radical before the fluorinating step (4).